

## 学 位 論 文 概 要

題 目 Atmospheric-Pressure Plasma-Enhanced Chemical Vapor Deposition for the Fabrication of TiO<sub>2</sub> UV-Protective Thin-Film

(大気圧プラズマ CVD による UV 遮蔽 TiO<sub>2</sub> 薄膜の開発)

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The overall objective of this research in doctoral education is to study the fabrication of TiO<sub>2</sub> UV-protective thin-film by atmospheric-pressure plasma-enhanced chemical vapor deposition (AP-PECVD) method.

**Chapter 1** is “**Introduction**”, which introduced the atmospheric pressure plasma, atmospheric-pressure plasma-enhanced chemical vapor deposition, and UV-protection, and presented the objective of this study. **Chapter 2** is “**Improving the UV-protective performance of AP-PECVD-derived TiO<sub>2</sub> thin-film**”, which focused on control of film thickness and roughness to improve the UV-protective performance of TiO<sub>2</sub> films prepared via AP-PECVD. The effects of substrate temperature and precursor concentration were investigated, and the results showed that an increase in both substrate temperature and precursor concentration reduced the roughness and improved the transparency to visible light without reducing the ability to block UV light. **Chapter 3** is “**TiO<sub>2</sub>-coated polymers and the stability against UV irradiation**”. The aim of this chapter was to improve the stability of polymers against UV irradiation through coating TiO<sub>2</sub> films using AP-PECVD method. The degradation of polymethylmethacrylate and polycarbonate under UV irradiation markedly slowed down after coating with TiO<sub>2</sub> films, which indicated that TiO<sub>2</sub>-coated polymers show significantly improved stability against UV irradiation. **Chapter 4** is “**Fabrication of large-area TiO<sub>2</sub> UV-protective thin-film**”. In actual production process, continuous fabrication and coating of large-area TiO<sub>2</sub> UV-protective film are needed. To solve this problem, generally, a moving stage for work pieces is used to meet the production requirements. Therefore, in this chapter, we focused on the feasibility of fabricating large-area TiO<sub>2</sub> UV-protective thin-film via AP-PECVD. **Chapter 5** is “**Summaries**”. The conclusion of each part was summarized in this chapter, and the perspective was proposed for a future research.